TRANSMITTAL OF INFORMATION	Docket No.								
Under 37 CFR 1.	97(b), (c), or	(d) (g)	8377/ETCH/SILICON						
In re Application of: Mui, et al.		2 2004 24							
Serial No. Filing		Examiner	Group Art Unit						
Title: METHOD FOR CONTROLLING		DIMESSIONS DURING AN	1765 ETCH PROCESS						
THE THOU FOR CONTROLLING	Addre	ADE	ETCH TROCESS						
	Commissione Alexandria, V	er for Patents							
	37 CFR	• •							
1. The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits; or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.									
37 CFR 1.97(c)									
2. The Information Disclosure Statement s prior to the mailing date of a Final Action that otherwise closes prosecution in the	n under 37 CFR	1.113, a Notice of Allowance under	er 37 CFR 1.311, or an Action						
37 CFR 1.97(d)									
3. The Information Disclosure Statement s on or before payment of the issue fee ar									
Required Statement	ts and/or Fe	ees Under 37 CFR 1.97(c) or (d)						
Each item of information contain	ed in the accomatent office in a	npanying Information Disclosure Si counterpart foreign application not	tatement was first cited in any						
No item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the undersigned person, after making reasonable inquiry, no item of information contained in the accompanying Information Disclosure Statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(2))									
The fee set forth in 37 CFR 1.1 account number 20-0782.	7(p). Please c	redit any overpayment or charge	any insufficiencies to deposit						
	37 CFR §	§1.704(d)							
4. Each item of information in the accomp foreign patent office in a counterpart applin 37 CFR §1.56(c) more than thirty days	eanying Informat	ion Disclosure Statement was cites communication was not received	I by any individual designated						
Mh Cal	Dated:	Pan 19, 2004							
Keith P. Taboada, Esq.	/ ,	Certificate of Mailin							
Reg. No. 45,150 Moser, Patterson & Sheridan, LLP Attorneys at Law 595 Shrewsbury Avenue, Suite 100 Shrewsbury, New Jersey 07702 732-530-9404		I certify that this document is beir with the U.S. Postal Service as fi and is addressed to the Commiss 1450, Alexandria, VA 22313-145 Signature of Person M Barbara	rst class mail under 37 CFR §1.8 sioner for Patents, P.O. Box						
	Typed or Printed Name of Person Mailing Correspondence								

Sheet 1 of 1 sheet(s)

U.S. Depar	tment	of Commerce. Pate	ent and Tradem	nark Office	Docket N		Serial No		
U.S. Department of Commerce, Patent and Trademark Office (Profesion 1449 modified)				8377/ETCH/SILICON					
MFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant Mui, et al.		Confirmation No.:7907		
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Use several meets if necessary)					Filing Date		Group		
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